

SPECIFICATION

DEVICE AND METHOD FOR SUPPLYING GAS WHILE DIVIDING TO CHAMBER FROM GAS SUPPLYING FACILITY EQUIPPED WITH FLOW CONTROLLER

5 This is a National Phase Application in Singapore of International Patent Application No. PCT/JP₂004/008117 filed June 10, 2004, which claims priority on Japanese Patent Application No. 2003-177134, filed June 20, 2003. The entire disclosures of the above patent applications are hereby incorporated by reference.

10 Field of the Invention

[0001] The present invention is to be used for semiconductor manufacturing facilities, and is concerned with improvements in supplying gas while automatically dividing to a chamber from a gas supplying facility equipped with a flow controller.

15 Background of the Invention

[0002] A device called a pressure type flow controller has been widely used for flow control of gas to be supplied to a chamber of a semiconductor manufacturing facility.

Figure 5 illustrates an example in the event that processing gas G is supplied into a chamber to form a silicon oxide film using a pressure type flow controller FCS.

20 A specified quantity Q of processing gas G is supplied to a pressure-reduced chamber C by using a vacuum pump Vp, and a quantity Q of processing gas G is discharged to a wafer H on the supporting device I through a gas discharger D.

[0003] On the other hand, the afore-mentioned pressure type flow controller FCS utilizes the relation that “when a critical condition $P_1 > \text{approx. } 2 \times P_2$ is maintained, a quantity Q of gas passing through an orifice L is determined only by gas pressure P_1 on the upstream side of the orifice, and is represented by the formula $Q = CP_1$ (where C is a constant dependent on the bore of the orifice L and gas temperature)”, thus a quantity Q on the downstream side of the orifice L being able to be held at a desired set value by regulating the afore-mentioned pressure P_1 with a control valve CV .

With Figure 5, P_0 designates supply pressure of processing gas G , P_m a manometer, F a filter, CPU a central processing unit, Q_s an input signal for a flow rate setting, and Q_e an output signal for control of the flow rate. A pressure type flow controller itself has been publicly disclosed with the TOKU-KAI-HEI No.8-338546, the TOKU-KAI-HEI No.11-63265 and others.

Therefore, detailed explanations are omitted herewith.

[0004] With the afore-mentioned flow controller FSC , it becomes an essential condition that, as stated above, gas pressure P_1 on the upstream side of the orifice and gas pressure P_2 on the downstream side of the orifice are within the afore-mentioned critical condition. The drawback is that the flow control cannot be performed because the critical expansion pressure condition is not satisfied, for example, when gas pressure P_2 on the downstream side of the orifice rises more than gas pressure P_1 on the upstream side of the orifice.

Another drawback is that flow control accuracy is lowered in reality when P_1/P_2 reaches closer the limit value of the afore-mentioned critical pressure condition with the rise of pressure P_2 on the downstream side of the orifice. Thus limiting the flow

control range capable of being used when pressure P_2 on the downstream side rises.

[0005] As above, various drawbacks are seen with the control of the gas flow rate by the pressure type flow controller when pressure P_2 on the downstream

5 side of the orifice L rises. However, the gas supply method to a chamber by using the said pressure type flow controller FCS allows the gas flow control with the high degree of accuracy easily to be performed, and makes it possible that a pressure regulating device with the high degree of accuracy at the gas supply source is not required to be provided, thus allowing considerable reductions of the costs in a gas supply facility, to
10 achieve excellent, practical effects.

[0006] On the other hand, a silicon wafer with a larger external diameter has been used for semiconductor manufacturing in recent years. In the case of the wafer H with an external diameter of 300mm ϕ , for example, there are required separate adjustments for
15 supply quantities of processing gas to the center part and the peripheral (edge) part respectively.

As a measure to handle the matter, processing gas can be supplied to the afore-mentioned center part and edge part respectively by providing separate branch supply lines GL_1 and GL_2 as shown in Figure 6, thus being able to supply processing gas
20 G without any difficulties from a gas supply source S with specified quantities Q_1 and Q_2 even with gas supply lines GL_1 and GL_2 wherewith a pressure type flow controller FCS.

[0007] However, to supply gas using gas supply lines GL_1 and GL_2 both of which are equipped with a pressure type flow controller FCS_1 and FCS_2 independently into a

chamber invites a rise in installation costs as well as upsizing of a semiconductor manufacturing facility, and is also found to be time-consuming for its maintenance. For these reasons, the method is undesirable.

5 [0008] To solve these problem, as shown in Figure 7, it is found desirable that the method wherewith flow rate Q_1 and Q_2 of branch gas supply lines GL_1 and GL_2 are controlled by branching two gas supply lines GL_1 and GL_2 from a pressure type flow controller FCS, and regulating flow rate control valves V_1 and V_2 equipped with the gas supply lines GL_1 and GL_2 respectively is employed.

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[0009] Among the general-purpose pressure type flow controllers FCS for a gas supply facility presently used, ones with flow rate control characteristics capable of being used within the range of 0~100Torr of pressure P_2 on the downstream side of the orifice under optimum conditions have been widely employed in general. Accordingly,
15 with these pressure type flow controllers FCS, the flow rate control range is considerably limited when pressure P_2 on the downstream side of the orifice exceeds approximately 100Torr, as described above, from the point of flow rate accuracy.

[0010] For example, let's assume that processing gas G of a flow rate $Q=300\text{SCCM}$ is
20 to be supplied to a chamber C through supply lines GL_1 and GL_2 at flow rates of $Q_1=130\text{SCCM}$ and $Q_2=170\text{SCCM}$ in Figure 7. With a gas supply facility not equipped with a pressure type flow controller FCS, firstly flow rate control valves V_1 and V_2 are closed, and next, the flow rate of processing gas is set to $Q=300\text{SCCM}$, and then flow rates Q_1 and Q_2 can be adjusted to the set value by regulating the degree of opening of

control valves V_1 and V_2 automatically or with reference of a flow meter (not illustrated).

[0011] However, in the event that a pressure type flow controller FCS is used for a
5 flow controller of the gas supply facility as illustrated in Figure 7, both control valves V_1
and V_2 are first placed in a state of being fully closed, and a flow rate Q (300SCCM) of
the pressure type flow controller FCS is set. Then, the degree of opening of both
control valves V_1 and V_2 are adjusted to the flow rate Q_1 (130SCCM) and Q_2 (170
SCCM) for branch supply lines GL_1 and GL_2 . This, however, finds it difficult to
10 control the flow rates accurately and quickly.

The reasons are that there is a possibility that the values of P_1/P_2 are out of the
threshold value of critical pressure conditions of the afore-mentioned pressure type flow
controller FCS due to the rise of pressure P_2 on the upstream side of both control valves
 V_1 and V_2 when opening of V_1 and V_2 are small, thus resulting in that the control flow
15 rate Q with the pressure type flow controller FCS becomes vastly different from the set
flow rate of $Q=300\text{SCCM}$.

[0012] To solve the afore-mentioned difficulties, inventors of the present invention
have applied for a patent, the TOKU-GAN-HEI No.2002-161086 by developing a
20 method to supply gas while dividing gas into a chamber from a gas supply facility.

[0013] This is a completely new idea of switching from the conventional and
well-worn method wherewith gas from a gas supply facility is supplied while dividing
for being controlled, that is, flow rate control valves V_1 and V_2 provided with branch

supply lines are put in a state of fully or near-fully closing, and then, both flow rate control valves V_1 and V_2 are gradually opened, while with the new method both flow rate control valves V_1 and V_2 are made to be in a state of fully or near-fully opening, and then, both flow rate control valves V_1 and V_2 are regulated to the direction of closing
5 step by step for the opening adjustment, thus making it possible that while a total flow quantity Q is controlled at the high degree of accuracy with the pressure type flow controller FCS, flow rates Q_1 and Q_2 are controlled by the pressure type division quantity controllers FV_1 and FV_2 provided with branch supply lines GL_1 and GL_2 at a desired flow rate ratio Q_1/Q_2 accurately and quickly.

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[0014] With the method, there will be no possibility that pressure P_2 on the downstream side of the orifice of the pressure type flow controller FCS rises sharply at the time of being divided even with processing gas from a gas supply facility provided with a pressure type flow controller FCS, thus making it possible that the total quantity
15 Q is accurately controlled at a desired flow rate value Q regardless of the flow control while dividing by means of a pressure type division quantity controllers FV_1 and FV_2 . Accordingly, excellent characteristics of a pressure type flow controller FCS can be utilized, thus making it possible that the flow division control while dividing is performed accurately and quickly, and also with a plurality of flow rate ratios Q_2/Q_1 .

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[0015] As stated above, the method employed in the TOKU-GAN-HEI No.2002-161086 made it possible that flow rates Q_1 and Q_2 of branch supply lines GL_1 and GL_2 are regulated at a desired flow rate ratio Q_1/Q_2 accurately and quickly. However, on the other hand, the method made the control complicated because it

employed two pressure type division quantity controllers FV_1 and FV_2 beside a pressure type flow controller FCS for regulating pressure on both sides, thus inviting another problem of facility costs becoming higher.

Patent Literature 1: TOKU-KAI-HEI No.8-338546 Public Bulletin

5 Patent Literature 2: TOKU-KAI-HEI No.11-632656 Public Bulletin

Disclosure of the Invention Object of the Invention

[0016] It is an object of the present invention to solve a problem that, with a conventional method wherewith gas is supplied while dividing to a chamber from a gas supply facility as illustrated in Figure 7, flow rate control accuracy is lowered when
10 critical pressure conditions are out of a threshold values due to that pressure P_2 on the upstream side of control valves V_1 and V_2 rises in the event that the degree of opening of control valves V_1 and V_2 are small.

It is also another object of the present invention to solve a problem that, with
15 techniques newly developed with the TOKU-GAN-HEI No.2002-161086, two pressure type division quantity controllers FV_1 and FV_2 are required beside a pressure type flow controller FCS, thus inviting high facility costs and making flow control complicated.

Means to Achieve the Objects

20 [0017] To solve the afore-mentioned problems, inventors of the present invention have developed a device and a method, simply structured and manufactured at low costs, for supplying gas while dividing to a chamber from a gas supply facility accurately and quickly.

[0018] The present invention in accordance with a first apparatus embodiment is fundamentally so constituted that, with a device for supplying a specified quantity Q of gas G while dividing at a specified flow rate ratio Q_1/Q_2 from a gas supply facility 1 provided with a flow controller QCS into a chamber C through a plurality of branch supply lines GL_1 and GL_2 and shower plates 3 and 4 fixed to the ends thereof, open/close valves OV_1 and OV_2 are provided with an afore-mentioned plurality of branch supply lines GL_1 and GL_2 respectively, and also a bypass line BL_1 on the downstream side of an open/close valve OV_1 and branched from the branch supply line GL_1 , a bypass line BL_2 on the downstream side of an open/close valve OV_2 and branched from the branch supply line GL_2 , a pressure type division quantity controller FV connected to the afore-mentioned bypass lines BL_1 and BL_2 , a pressure sensor PS_1 to measure pressure inside the branch supply line GL_1 , and a pressure sensor PS_2 to measure pressure inside the branch supply line GL_2 are provided.

[0019] The present invention in accordance with a second apparatus embodiment further modifies the first apparatus embodiment and is fundamentally so constituted that a control device CT to regulate the degree of opening of a pressure type division quantity controller FV is provided to reduce the difference between actual pressure of the branch supply line and set pressure to reach the specified flow rate ratio Q_1/Q_2 by comparing either one of set pressure PI_1 or PI_2 of the branch supply lines GL_1 and GL_2 to reach the specified flow rate ratio Q_1/Q_2 with corresponding actual pressure PT_1 or PT_2 of the branch supply lines GL_1 or GL_2 measured by the pressure sensor PS_1 or the pressure sensor PS_2 .

[0020] The present invention in accordance with a third apparatus embodiment, further modifies the first apparatus embodiment and the second apparatus embodiment and is fundamentally so constituted that an open/close valve OV_1 and an open/close valve OV_2 are pneumatically operated, and a switch valve SV is provided for
5 supplying actuating air to the open/close valve OV_1 and the open/close valve OV_2 .

[0021] The present invention as claimed in Claim 4 according to Claim 1, Claim 2 or Claim 3 is fundamentally so constituted that an open/close valve OV_1 and an open/close valve OV_2 are made to be integrated.

[0022] The present invention as claimed in accordance with a fourth apparatus embodiment, further modifies the first apparatus embodiment the second apparatus embodiment and the third apparatus embodiment and is fundamentally so constituted that a pressure type flow controller FCS is used for a flow controller QCS.

[0023] The present invention in accordance with a first apparatus embodiment, is fundamentally so constituted that, with a method for supplying a specified quantity Q of gas G while dividing at a specified flow rate ratio Q_1/Q_2 from a gas supply facility 1 provided with a flow controller QCS into a chamber C through a plurality of branch
15 supply lines GL_1 and GL_2 and shower plates 3 and 4 fixed to the ends thereof, open/close valves OV_1 and OV_2 are installed on an afore-mentioned plurality of branch supply lines GL_1 and GL_2 respectively, and also a bypass line BL_1 on the downstream side of an open/close valve OV_1 and branched from the branch supply line GL_1 , a bypass line BL_2 on the downstream side of an open/close valve OV_2 and branched from the branch
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supply line GL₂, a pressure type division quantity controller FV connected to the
afore-mentioned bypass lines BL₁ and BL₂, and further a pressure sensor PS₁ to measure
pressure inside the branch supply line GL₁, and a pressure sensor PS₂ to measure
pressure inside the branch supply line GL₂ are provided so that a total quantity $Q=Q_1+Q_2$
5 of gas is supplied while dividing into a chamber C at desired division quantities Q₁ and
Q₂ by opening the open/close valve of the branch supply line which has a larger flow
rate to regulate the degree of opening of the afore-mentioned pressure type division
quantity controller FV, and adjusting the flow rate of the branch supply line which has
the larger flow rate to the branch supply line which has the smaller flow rate, thus
10 regulating pressure in the branch supply line GL₁ and the branch supply line GL₂.

[0024] The present invention in accordance with a second method embodiment,
further modifies the first method embodiment and is so practised that the degree of
opening of a pressure type division quantity controller FV is regulated to reduce the
15 difference between actual pressure of a branch supply line and set pressure to reach a
specified flow rate ratio Q₁/Q₂ by comparing either one of set pressure PI₁ or PI₂ of
branch supply lines GL₁ and GL₂ to reach the specified flow rate ratio Q₁/Q₂ with
corresponding actual pressure PT₁ or PT₂ of the branch supply lines GL₁ and GL₂
measured by the pressure sensor PS₁ or the pressure sensor PS₂.

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[0025] The present invention, in accordance with a second method embodiment,
further modifies the first method embodiment and is so practised that an open/close
valve OV₁ and an open/close valve OV₂ are pneumatically operated, and a switch valve
SV is provided for supplying actuating air to the open/close valve OV₁ and the

open/close valve OV_2 so that the open/close valve of the branch supply line with the larger supply quantity is made open by the switch valve SV.

[0026] The present invention, in accordance with a fourth method embodiment, further
5 modifies the first method embodiment, the second method embodiment and the third method embodiment and 8 is so practised that a pressure type flow controller is used for a flow controller QCS.

Effects of the Invention

10 [0027] The present invention provides a device for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller which is so constituted that, with a device for supplying a specified quantity Q of processing gas while dividing at a specified flow rate ratio Q_2/Q_1 from a gas supply facility 1 equipped with a flow controller QCS into a chamber C through a plurality of branch
15 supply lines GL_1 and GL_2 and shower plates 3 and 4 fixed to the ends thereof, a division quantity controller 2 comprising an open/close valves OV_1 and OV_2 installed on an afore-mentioned plurality of branch supply lines GL_1 and GL_2 respectively, a bypass line BL_1 branched from a branch supply line GL_1 on the downstream side of the open/close valve OV_1 , a bypass line BL_2 branched from a branch supply line GL_2 on the downstream
20 side of the open/close valve OV_2 , a pressure type division quantity controller FV connected to the bypass line BL_1 and the bypass line BL_2 , a pressure sensor PS_1 to measure pressure inside the branch supply line GL_1 , and a pressure sensor PS_2 to measure pressure inside the branch supply line GL_2 is installed between the afore-mentioned gas supply facility 1 and a chamber C so that a specified quantity Q of

gas is supplied while dividing into the chamber at a specified flow rate ratio Q_1/Q_2 through shower plates 3 and 4 fixed to the ends of branch supply lines GL_1 and GL_2 .

As a result, pressure control on a number of flow rate ratios Q_2/Q_1 becomes possible accurately and quickly with the pressure type division quantity controller, thus achieving an excellent effect of making facility costs lowered.

[0028] The present invention provides a method for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller characterized by that, with a method for supplying a specified quantity Q of processing gas while dividing at a specified flow rate ratio Q_1/Q_2 from a gas supply facility 1 equipped with a flow controller QCS into a chamber through a plurality of branch supply lines GL_1 and GL_2 and shower plates 3 and 4 fixed to the ends thereof, a division quantity controller 2 comprising an open/close valves OV_1 and OV_2 installed on an afore-mentioned plurality of branch supply lines GL_1 and GL_2 respectively, a bypass line BL_1 branched from a branch supply line GL_1 on the downstream side of the open/close valve OV_1 , bypass line BL_2 branched from a branch supply line GL_2 , a pressure type division quantity controller FV connected to the bypass line BL_1 and the bypass line BL_2 , a pressure sensor PS_1 to measure pressure inside the branch supply line GL_1 , and a pressure sensor PS_2 to measure pressure inside the branch supply line GL_2 is installed between the afore-mentioned gas supply facility 1 and a chamber C, and also that a total quantity $Q=Q_1+Q_2$ of gas while dividing is supplied into the afore-mentioned chamber C at desired flow rates Q_1 and Q_2 by regulating pressure of the branch supply line GL_1 and the branch supply line GL_2 by opening the open/close valve of a branch supply line having a larger flow rate, adjusting the flow rate of the branch supply line which has a larger flow

rate by regulating the degree of opening of the afore-mentioned pressure type division quantity controller FV, thus regulating pressure in the branch supply line GL₁ and GL₂.

As a result, pressure control on a number of flow rate ratios Q_2/Q_1 can be performed accurately and quickly with one set of pressure type division quantity
5 controller, thus achieving excellent effects of making facility costs lowered and pressure control easier.

Brief Description of the Drawings

[0029] Figure 1 is an overall schematic diagram to explain a device and a method for
10 supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller according to the present invention.

Figure 2 is a basic block diagram of a pressure type division quantity controller FV.

Figure 3 is lines (computed values) to illustrate the relations between set
15 pressure (PI₁ and PI₂) and a division flow rate ratio Q_2/Q_1 in the event that shower plated 3 and 4 to be used are made to be a Pattern 1 with supply while dividing in Figure 1.

Figure 4 is lines (computed values) to illustrate the same relations in the event that shower plates 3 and 4 to be used are made to be a Pattern 2 as with Figure 3.

Figure 5 is an explanatory drawing to show a method for supplying
20 processing gas to a chamber by using a conventional pressure type flow controller FCS.

Figure 6 is an explanatory drawing to show the case wherein processing gas is supplied to a chamber C from a single gas supply source S by using a plurality of pressure type flow controllers.

Figure 7 is an explanatory drawing to show the case wherein processing gas is

supplied to a chamber C from a gas supply source equipped with a pressure type flow controller by using control valves.

List of Reference Characters and Numerals

5	[0030]	BL ₁ BL ₂	Bypass lines
		C	Chamber
		D	Gas discharger
		Dc	Gas discharger for the center part
		De	Gas discharger for the edge part
10		FV	Pressure type division quantity controller
		GL ₁	Branch supply line for the center part
		GL ₂	Branch supply line for the edge part
		OV ₁ OV ₂	Open/close valves
		PT ₁ PT ₂	Pressure in branch supply lines
15		P	Pressure inside a chamber
		PS ₁ PS ₂	Pressure sensors of branch supply lines
		QCS	Flow controller
		SV	Electric switch valve
		1	Gas supply facility
20		2	Division quantity controller
		3	Shower plate of a gas discharger for the center part
		3a	Orifice hole made in a shower plate
		4	Shower plate of a gas discharger for the edge part
		4a	Orifice hole made in a shower plate

Best Mode to Carry Out the Invention

[0031] The embodiment in accordance with the present invention is described hereunder with reference to the drawings.

5 Figure 1 is an overall schematic diagram to explain a device and a method for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller QCS according to the present invention. In Figure 1, a gas supply facility 1 comprises a supply source S of processing gas G, a gas main valve Vo, a flow controller QCS and the like. A division quantity controller 2 comprises a pressure type
10 division quantity controller FV, a communication control circuit CT and the like.

[0032] Further, in Figure 1, C designates a chamber, D a gas discharger, Dc a gas discharger for the center part, De a gas discharger for the edge part, GL₁ a branch supply line for the center part, GL₂ a branch supply line for the edge part, Q a total quantity of
15 gas, Q₁ Q₂ flow rates while dividing, PT₁ PT₂ pressure in branch supply lines GL₁ and GL₂, P₃ pressure inside a chamber C, PS₁ PS₂ pressure sensors of branch supply lines GL₁ and GL₂, 3 a shower plate of a gas discharger Dc for the center part, 3a an orifice hole made on the shower plate, 4 shower plate of a gas discharger De for the
edge part, and 4a an orifice hole made on the shower plate.

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[0033] In addition, in Figure 1, EL₁ EL₂ designate signal connection lines of a communication control circuit CT with pressure sensors PS₁ and PS₂, EL₃ a signal connection line of a communication control circuit with an electric switch valve SV, and T₁ a power source/signal input terminal.

[0034] The afore-mentioned gas supply facility 1 comprises a processing gas supply source S, a plurality of flow controllers QCS and the like. Any type flow controllers QCS can be employed as a flow controller QCS as long as it functions accurately and quickly. A pressure type flow controller FCS illustrated in the afore-shown Figure 5 has
5 been used herewith for a flow controller QCS. When a specified flow rate setting signal Q_s is inputted to a control unit (CPU), pressure P_1 on the upstream side of an orifice L is regulated by a control valve CV so that a flow rate Q on the downstream side is automatically adjusted to the set flow rate Q_s .

Also, a control flow rate output signal Q_e corresponding to the adjusted flow
10 rate is outputted from the control unit (CPU). If it is found that the deviation between the flow rate setting input signal Q_s and the afore-mentioned control flow rate setting signal Q_e exceeds the prescribed time, an input/output deviation abnormality signal is transmitted from the CPU (not illustrated in Figure 5) as stated later.

[0035] The afore-mentioned division quantity controller 2 comprises a plural number of open/close valves OV_1 and OV_2 , a pressure type division quantity controller FV, a communication control circuit CT to control these, an electric switch valve SV for opening and closing of OV_1 and OV_2 , orifice plates 3 and 4 connected to the ends of branch supply lines, and the like.

[0036] As shown in Figure 2, the afore-mentioned pressure type division quantity controller comprises a control valve CV, a driving control part (CPU) for the control valve CV and the like, to regulate the degree of opening of the control valve CV through the mediation of the driving unit part (CPU) with the control signal inputted CT through

the line EL_3 from the communication circuit CT.

With the embodiment in Figure 2, a piezo-driving stroke amplification type metal diaphragm valve is employed for a control valve CV of the afore-mentioned pressure type division quantity controller FV so that it is easily adaptable even when the
5 flow rates Q_1 and Q_2 are large.

[0037] When processing gas G is supplied into a chamber C through orifice holes 3a and 4a made on shower plates 3 and 4 respectively, division quantities Q_1 and Q_2 can be controlled, as in the case of the orifice of a flow controller QCS, that is, a division
10 quantity Q_1 is controlled with a formula $Q_1=C_1PI_1$ by adjusting PI_1 if the relationships $PI_1 > 2P_3$ are maintained between pressure P_3 inside a chamber C and pressure PI_1 on the upstream side of the orifice hole 3a of the orifice plate 3 for the center part.

Similarly, a division quantity Q_2 is controlled with a formula $Q_2=C_2PI_2$ by PI_2 if the relationships $PI_2 > 2P_3$ are maintained between pressure P_3 inside a chamber C and
15 pressure PI_2 on the upstream side of the orifice hole 4a of the shower plate 4 for the edge part, (where C_1 and C_2 are constants dependent on the cross-sectional areas of the orifice holes 3a and 4a, their shapes or gas temperature).

[0038] Referring to Figure 1, the afore-mentioned communication control circuit CT
20 is provided with a power source/signal input terminal T_1 , and connected to a pressure type division quantity controller FV and an electric switch valve through the mediation of signal connection lines EL_3 and EL_4 .

[0039] An open/close valve OV is pneumatically operated. It is of a normal open type

wherewith it is open under a state of driving air not being supplied, but both open/close valves OV_1 and OV_2 are normally being closed when a division quantity controller 2 is in a state of halting.

- 5 [0040] When a starting signal, a total flow quantity Q , a desire flow rate ratio Q_2/Q_1 , a combination pattern of shower plates 3 and 4 and the like are inputted through the mediation of the power source/signal input terminal T_1 , a communication control circuit CT makes the branch supply line with pressure set low out of set pressure PI_1 and PI_2 a subject-to-control branch supply line, while the remaining branch supply line a
10 non-subject-to-control branch supply line as patterns of set pressure ratio PI_2/PI_1 show in Table 1.

A communication control circuit CT opens an open/close valve of the non-subject-to-control branch supply line while it closes an open/close valve of the subject-to-control branch supply line.

- 15 Further, a communication control circuit CT determines values Q_1 and Q_2 with given total flow quantity Q and flow rate ratio.

[0041] [Table 1]

Set Pressure Ratio – Subject-to-control • Open/close valves operation command

Set pressure ratio PI_2/PI_1	Subject-to-control	Open/close valve operation command	
		OV_1	OV_2
> 1	PI_1	Close	Open
$= 1$	NONE	Open	Open
< 1	PI_2	Open	Close

[0042] By inputting a specified signal to the communication control circuit CT, pressure PT on the subject-to-control branch supply line side is regulated with the pressure type quantity controller FV.

Namely, a communication control circuit CT starts comparing set values with
5 actual pressure by the pressure signal measured and transmitted by a pressure sensor PS of the subject-to-control branch supply line, and a signal is transmitted to regulate the degree of opening of the division quantity controller FV so that the difference is reduced. Concretely, in the event that it is found with the comparison results that actual pressure is lower than set pressure, the degree of opening of the division quantity controller FV is
10 made wider to raise pressure PT of the subject-to-control branch supply line. When the results of the comparison are found to be reverse, that is, actual pressure is higher than set pressure, the degree of opening of the division quantity controller FV is made narrower to lower pressure PT of the subject-to-control branch supply line.

15 [0043] Set pressure is determined beforehand by computation of the relationships of supply flow rates of shower plates with pressure.

The set pressure ratio is determined from the results of the computation based on the flow rate ratio Q_2/Q_1 supplied to branch supply lines GL_1 and GL_2 as shown in Table 2 and Table 3.

20 [0044] [Table 2]

[Set pressure ratio/Subject-to-control division quantity/Open/close valve operation command] to flow rate ratios PATTERN 1

Flow rate ratio Q_2/Q_1	Set pressure ratio PI_2/PI_1	Subject-to-control division flow quantity	Open/close valve operation command
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			OV ₁	OV ₂
4/1	2.079 > 1	PI ₁	Close	Open
3/1	1.795 > 1	PI ₁	Close	Open
2/1	1.473 > 1	PI ₁	Close	Open
1/1	1.041 > 1	PI ₁	Close	Open
1/2	0.736 < 1	PI ₂	Open	Close
1/3	0.601 < 1	PI ₂	Open	Close
1/4	0.520 < 1	PI ₂	Open	Close

[0045] [Table 3]

[Set pressure ratio/Subject-to-control division quantity/Open/close valve
operation command] to flow rate ratios PATTERN 2

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Flow rate ratio Q ₂ /Q ₁	Set pressure ratio PI ₂ /PI ₁	Subject-to-control division flow quantity	Open/close valve operation command	
			OV ₁	OV ₂
4/1	2.008 > 1	PI ₁	Close	Open
3/1	1.795 > 1	PI ₁	Close	Open
2/1	1.473 > 1	PI ₁	Close	Open
1/1	1.041 > 1	PI ₁	Close	Open
1/2	0.736 < 1	PI ₂	Open	Close
1/3	0.601 < 1	PI ₂	Open	Close
1/4	0.520 < 1	PI ₂	Open	Close

[0046] With the present embodiment, for shower plates (orifice plates) 3 and 4 of gas dischargers Dc and De, two sets of shower plate, that is, Dc₁ having 420 orifice holes 3a and Dc₂ having 480 orifice holes 3a are ready for the afore-mentioned shower plate 3 for the center part, and similarly another two sets of shower plate, that is, De₁ having 360 orifice holes 4a and De₂ having 476 orifice holes 4a are also ready for the shower plate 4 for the edge part.

[0047] Furthermore, the afore-mentioned flow rate ratio Q_2/Q_1 can be set at 1/1, 1/2, 1/3, 1/4, 2/1, 3/1 or 4/1. Set pressure computed on this (or set pressure specified by the gas supply chamber side) and set pressure ratio are inputted to the input terminal T₁.

[0048] As described later, set pressure and set pressure ratio listed in the above-shown Table 2 and Table 3 are determined by computing set pressure PI₁ and PI₂ on the upstream side of orifice holes 3a and 4a required to discharge the afore-mentioned specified flow quantities Q₁ and Q₂ of gas G judging with the bore sizes and numbers of orifice holes 3a and 4a of the shower plates 3 and 4 to be connected to the ends of branch gas supply lines. Further, it shows the ratio PI₂/PI₁ determined by computing with necessary set pressure PI₂ and PI₁ on the upstream side obtained from the computation.

[0049] For combinations of the afore-mentioned shower plates 3 and 4, there are chosen beforehand a combination (hereinafter called Pattern 1) of a shower plate 3 having 420 orifice holes 3a and a shower plate 4 having 360 orifice holes 4a, and

combination (hereinafter called Pattern 2) of a shower plate 3 having 480 orifice holes 3a and a shower plate 4 having 476 orifice holes 4a.

[0050] The relationship of the afore-mentioned division flow rates Q_1 and Q_2 and pressure PI_1 and PI_2 are formulated by using the following equations of conductance.

That is, the flow rate Q of gas passing through a pipe is expressed by $Q=C \times (P_1 - P_2) \dots (1)$ and $C=182 \times D^4 \times (P_1 + P_2)/2 \times 1/L \dots (2)$, where C represents a conductance (L/sec), D the diameter of a pipe (cm), L the length of a pipe (cm), P_1 upstream pressure of a pipe (Torr), P_2 downstream pressure of a pipe (Torr) and Q a flow rate (Torr • L/sec).

With the above equations (1) and (2), internal pressure (PI_1 and PI_2) on the upstream side of a shower plate is computed by using the outer diameter of the orifice hole of the shower plate as D , the length of the orifice hole of the shower plate as L , the internal pressure of a chamber ($P_3 = 0.015$ Torr) as downstream side pressure P_2 , and a flow rate per an orifice hole as a flow rate Q respectively.

[0051] Figure 3 is numerical values shown as a graph illustrating the relationships, in the event (Pattern 1) that a shower plate 3 of the gas discharger Dc for the center part having 420 orifice holes with an internal diameter of 0.2mm ϕ and a shower plate 4 of the gas discharger De for the edge part having 360 orifice holes with an internal diameter of 0.2mm ϕ are combined, of a total flow rate (a whole flow rate) Q , control pressure PT_1 for the center part and control pressure PT_2 for the edge part are computed making a flow rate ratio ($E/C=Q_2/Q_1$) as a parameter. For example, in case of $Q=1600, 1200, 800, 400$ and 100 SCCM at $Q_2/Q_1=1$, the mean value of the ratio PI_2/PI_1 of control

pressure PI_2 on the edge part side and control pressure PI_1 on the center part side becomes 1.041.

[0052] Similarly, Figure 4 is numerical values shown as a graph in the event (Pattern
5 2) that a shower plate 3 for a gas discharger D_c for the center part having 480 orifice
holes with an internal diameter of 0.2mm ϕ and a shower plate 4 for a gas discharger D_e
for the edge part having 476 orifice holes with an internal diameter are combined. For
example, in case of $Q=1600, 1200, 800, 400$ and 100SCCM at Q_2/Q_1 , the mean value of
the ratio PI_2/PI_1 of control pressure PI_2 on the edge part side and control pressure PI_1 on
10 the center part side becomes 1.001.

[0053] Table 2 and Table 3 illustrate all computed values that show the relationships
of the flow rate ratio Q_2/Q_1 and the ratio PI_2/PI_1 of control pressure PI_2 on the edge part
side and control pressure PI_1 on the center part side with Pattern 1 and Pattern 2 shown
15 in Figure 3 and Figure 4. For example, Figure 3 shows that the ratio PI_2/PI_1 of control
pressure PI_2 on the edge part side and control pressure PI_1 on the center part side
becomes mathematically 1.041 in case that combination of shower plates 3 and 4 to be
used is made to be Pattern 1, and that the flow rate ratio Q_2/Q_1 is 1.

20 [0054] A method for supplying gas while dividing to a chamber according to the
present invention is explained hereafter. Referring to Figure 1 and Figure 2, both
open/close valves OV_1 and OV_2 are fully closed in case that a starting signal is not
inputted to a communication control circuit CT.

[0055] To supply a total quantity Q of gas while dividing at a specified ratio Q_2/Q_1 (for example, $Q_2/Q_1=1/2$), a total flow quantity Q , a combination pattern of shower plates 3 and 4 of gas dischargers D_c and D_e connected to the ends of branch supply lines GL_1 and GL_2 , and a desired flow rate ratio Q_2/Q_1 are inputted to a communication control
5 circuit CT. A control pressure ratio PI_2/PI_1 corresponding to shower plates 3 and 4 and a flow rate ratio Q_2/Q_1 is inputted as a set signal.

Next, a subject-to-control flow while dividing and a non-subject-to-control flow while dividing are determined by a communication control circuit CT based on given total quantity Q , a flow rate ratio Q_2/Q_1 and set pressure PI_1 and PI_2 . Then an
10 open/close valve OV of a non-subject-to-control branch supply line is opened, while an open/close valve OV of a non-subject-to-control branch supply line is closed.

[0056] For example, upon receiving a signal indicating a total flow rate Q of 1200SCCM, Pattern 1 of combination patterns of shower plate 3 and 4, a branch flow
15 rate ratio $Q_2/Q_1=1/2$, set pressure PI_1 and set pressure PI_2 , a communication control circuit CT determines a branch supply line GL_1 corresponding to PI_1 which set pressure is set lower out of set pressure PI_1 and PI_2 to be a subject-to-control branch supply line, while a remaining branch supply line GL_2 to be a non-subject-to-control branch supply line.

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[0057] An open/close valve OV_2 of the non-subject-to-control branch supply line GL_2 is opened, while an open/close valve OV_1 of the subject-to-control branch supply line GL_1 is closed by the communication control circuit CT.

The communication control circuit CT compares set pressure PI_1 with actual

pressure PT_1 by the pressure signal measured and transmitted by the pressure sensor PS_1 of the subject-to-control branch supply line GL_1 .

[0058] The communication control circuit CT compares set pressure PI_1 of a
5 subject-to-control branch supply line GL_1 with actual pressure PT_1 , to transmit a signal to regulate the degree of opening of a division quantity controller FV to reduce the difference.

Namely, in the event that comparison results found that actual pressure PT_1 is lower than set pressure PI_1 , the degree of opening of the division quantity controller FV
10 is made wider to raise pressure of the subject-to-control branch supply line PL_1 . With the reverse results that actual pressure PT_1 is higher than set pressure PI_1 , the degree of opening of the division quantity controller FV is made narrower to lower pressure of the subject-to-control branch supply line PL_1 .

15 [0059] With the communication control circuit CT, set pressure PI_1 of the subject-to-control branch supply line GL_1 and actual pressure are compared. When there is found no difference, or the difference is converged on the range of difference set in advance, the degree of opening of the division quantity controller FV is maintained, thus an automatic flow division control being completed.

20 Namely, a specified quantity Q of raw gas G from a gas supply source S is supplied to a wafer H into a chamber C through gas dischargers Dc and De while dividing at a specified flow rate ratio Q_1/Q_2 .

[0060] Also, with the communication control circuit CT, set pressure PI_1 and actual

pressure PT_1 are compared. When there is found no difference, or the difference is converged on the range of difference set in advance, the degree of opening of the division quantity controller FV is maintained, thus an automatic flow division control being completed. However, in the event that actual pressure PT_1 fluctuates due to temperature changes or any other reasons, and the difference with set pressure PI_1 comes to exceed the difference set in advance, a communication control circuit restarts to regulate the degree of opening of the division quantity controller FV.

[0061] With the embodiment, it is so constituted that a starting signal, a total flow quantity Q , a desired flow rate ratio Q_2/Q_1 , combination patterns of shower plates 3 and 4, set pressure PI_1 and PI_2 and the like are inputted to a communication control circuit CT through a power source/signal input terminal. However, it can be so constituted that a communication control circuit CT determines a subject-to-control branch supply line and its set pressure from the signals of the afore-mentioned total flow quantity Q , a flow rate ratio Q_2/Q_1 and the like and the data computed in advance.

Feasibility of Industrial Use

[0062] The present invention can be applied to facilities wherewith fluids are supplied while dividing under critical pressure conditions. For example, it can be utilized with a chamber in semiconductor manufacturing facilities or with a chamber in facilities for manufacturing chemical or pharmaceutical products.

CLAIMS

1. A device for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller, comprising

5 a device for supplying a specified quantity of gas while dividing at a specified flow rate ratio Q_1/Q_2 from a gas supply facility provided with a flow controller into a chamber through a plurality of branch supply lines including a first branch supply line and a second branch supply line and shower plates are fixed to ends of the first branch supply line and the second branch supply line;

10 a first open/close valve and a second open/close valve are installed on the first branch supply line and the second branch supply line respectively;

a first bypass line is disposed on a downstream side of the first open/close valve and branched from the first branch supply line;

15 a second bypass line is disposed on the downstream side of the second open/close valve and branched from the second branch supply line;

a pressure type division quantity controller is connected to the first bypass line and the second bypass line;

a first pressure sensor is disposed to measure pressure inside the first branch supply line and

20 a second pressure sensor is disposed to measure pressure inside the second branch supply line wherein Q_1 and Q_2 are specified quantities of gas supplied to the first branch supply line and the second branch supply line, respectively.

2. A device for supplying gas while dividing to a chamber from a gas supply

facility equipped with a flow controller as claimed in Claim 1 wherein a control device is disposed to regulate a degree of opening of the pressure type division quantity controller to reduce a difference between actual pressure of a branch supply line and set pressure to reach the specified flow rate ratio Q_1/Q_2 by comparing either one of a first set pressure or a second set pressure, respectively, of the first branch supply line and the second branch supply line to reach the specified flow rate ratio Q_1/Q_2 with corresponding first actual pressure or second actual pressure of the first branch supply line and the second branch supply line measured by the pressure sensor of the second pressure sensor.

10

3. A device for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller as claimed in Claim 1 wherein the first an open/close valve and the second open/close valve are pneumatically operated, and a switch valve is disposed to supply actuating air to the first open/close valve and the second open/close valve.

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4. A device for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller as claimed in Claim 1 wherein the first open/close valve and the second open/close valve are made to be integrated.

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5. A device for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller as claimed in Claim 1 wherein a pressure type flow controller FCS is used for a flow controller QCS.

6. A method for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller characterized in that, with a method for supplying a specified quantity Q of gas G while dividing at a specified flow rate ratio Q_1/Q_2 from a gas supply facility 1 provided with a flow controller QCS into a chamber C through a plurality of branch supply lines GL_1 and GL_2 and shower plates 3 and 4 fixed to the ends thereof, open/close valves OV_1 and OV_2 are installed on an afore-mentioned plurality of branch supply lines GL_1 and GL_2 respectively, and also a bypass line BL_1 on the downstream side of an open/close valve OV_1 and branched from the branch supply line GL_1 and a bypass line BL_2 on the downstream side of an open/close valve OV_2 and branched from the branch supply line GL_2 , a pressure type division quantity controller FV connected to the afore-mentioned bypass lines BL_1 and BL_2 , a pressure sensor PS_1 to measure pressure inside the branch supply line GL_1 and a pressure sensor PS_2 to measure pressure inside the branch supply line GL_2 are provided so that a total quantity $Q=Q_1+Q_2$ of gas is supplied while dividing into a chamber C at desired division quantities Q_1 and Q_2 by opening the open/close valve of the branch supply line which has a larger flow rate, then adjusting the flow rate of the branch supply line which has the larger flow rate to the branch supply line which has the smaller flow rate to the branch supply line by regulating the degree of opening the afore-mentioned pressure type division quantity controller FV, thus regulating pressure in the branch supply lines GL_1 and GL_2 .

7. A method for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller as claimed in Claim 6 wherein the degree of opening of the pressure type division quantity controller is regulated to reduce a difference between actual pressure of a branch supply line and set pressure to reach the

specified flow rate ratio Q_1/Q_2 by comparing either one of a first set pressure or a second set pressure, respectively, of the first branch supply line and the second branch supply line to reach the specified flow rate ratio Q_1/Q_2 with corresponding first actual pressure or second actual pressure of the first branch supply line and the second branch supply line measured by the first pressure sensor or the second pressure sensor.

8. A method for supplying gas while dividing to a chamber from a gas supply facility equipped with a flow controller as claimed in Claim 6, wherein the first open/close valve and the second open/close valve are pneumatically operated, and a switch valve is disposed to supply actuating air to the first open/close valve and the second open/close valve so that the open/close valve of the one branch supply line with the larger supply quantity is opened by the switch valve.

9. A method for supplying gas while dividing to a chamber from a gas supply facility equipped a flow controller as claimed in Claim 6 wherein a pressure type flow controller is used for the flow controller.